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## **TC 3700 Inventor Search Program**

See attached inventor searches for applications and/or patents to help resolve questions of overlapping subject matter. These searches are provided as an initial examination aid: examiners should perform updated or expanded PALM or EAST inventors searches as appropriate.

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**Serial Number: 10788700**

**1.) See attached printout of inventors listed in  
PALM**

**2.) See attached EAST Inventor Search  
Printout shows Inventor search terms**

US 20060035464 A1	US- PGPUB	20060216	16	Method of planarizing a semiconductor substrate	438/690	438/745	Sreenivasan; Sidlgata V.
US 20060005657 A1	US- PGPUB	20060112	17	Method and system to control movement of a body for nano-scale manufacturing	74/490.07		Choi; Byung-Jin et al.
US 20060001857 A1	US- PGPUB	20060105		Apparatus to vary dimensions of a substrate during nano-scale manufacturing	355/72		Cherala; Anshuman et al.
US 20060001194 A1	US- PGPUB	20060105		System for varying dimensions of a substrate during nanoscale manufacturing	264/320		Cherala; Anshuman et al.
US 20050275311 A1	US- PGPUB	20051215		Compliant device for nano-scale manufacturing	310/323.05		Choi; Byung-Jin et al.
US 20050275251 A1	US- PGPUB	20051215		Compliant device for nano-scale manufacturing	297/40		Choi; Byung-Jin et al.
US 20050274219 A1	US- PGPUB	20051215		Method and system to control movement of a body for nano-scale manufacturing	74/490.07		Choi; Byung-Jin et al.
US 20050271955 A1	US- PGPUB	20051208		System and method for improvement of alignment and overlay for microlithography	430/22		Cherala, Anshuman et al.
US 20050270516 A1	US- PGPUB	20051208		System for magnification and distortion correction during	355/72		Cherala, Anshuman et al.

				nano-scale manufacturing			
US 20050270312 A1	US- PGPUB	20051208		Fluid dispensing and drop-on-demand dispensing for nano-scale manufacturing	347/1		Lad, Pankaj B. et al.
US 20050269745 A1	US- PGPUB	20051208		Method of varying dimensions of a substrate during nano-scale manufacturing	264/320		Cherala, Anshuman et al.
US 20050266587 A1	US- PGPUB	20051201		Substrate support method	438/5	438/458	Nimmakayala, Pawan Kumar et al.
US 20050264134 A1	US- PGPUB	20051201		Adaptive shape substrate support system	310/311		GanapathiSubramanian, Mahadevan et al.
US 20050264132 A1	US- PGPUB	20051201		Apparatus to control displacement of a body spaced-apart from a surface	310/311		Choi, Byung Jin et al.
US 20050263249 A1	US- PGPUB	20051201		Substrate support system	156/345.51		Nimmakayala, Pawan Kumar et al.
US 20050263077 A1	US- PGPUB	20051201		Adaptive shape substrate support method	118/728		GanapathiSubramanian, Mahadevan et al.
US 20050260848 A1	US- PGPUB	20051124		Method of forming a recessed structure employing a reverse tone process	438/637		Sreenivasan, Sidlgata V.
US 20050260295 A1	US- PGPUB	20051124		Remote center compliant flexure device	425/149	425/408	Choi, Byung-Jin et al.
US 20050253307 A1	US- PGPUB	20051117		Method of patterning a conductive layer on a substrate	264/494	264/104; 264/105; 264/236; 264/293;	Sreenivasan, Sidlgata V.

					264/310	
US 20050236360 A1	US- PGPUB	20051027		Compliant hard template for UV imprinting	216/41	Watts, Michael P.C. et al.
US 20050189676 A1	US- PGPUB	20050901		Full-wafer or large area imprinting with multiple separated sub- fields for high throughput lithography	264/225	Sreenivasan, Sidlgata V.
US 20050185169 A1	US- PGPUB	20050825		Method and system to measure characteristics of a film disposed on a substrate	356/237.1 356/399; 356/625	McMackin, Ian M. et al.
US 20050160011 A1	US- PGPUB	20050721		Method for concurrently employing differing materials to form a layer on a substrate	705/26	Sreenivasan, Sidlgata V. et al.
US 20050106321 A1	US- PGPUB	20050519		Dispense geometry to achieve high- speed filling and throughput	427/258 427/421.1; 427/532	McMackin, Ian M. et al.
US 20050098534 A1	US- PGPUB	20050512		Formation of conductive templates employing indium tin oxide	216/52 216/44; 430/275.1; 430/277.1	Sreenivasan, Sidlgata V. et al.
US 20050089774 A1	US- PGPUB	20050428		METHOD TO CONTROL THE RELATIVE POSITION BETWEEN A BODY AND A SURFACE	430/22 355/18; 355/72; 396/428; 430/30	Choi, Byung Jin et al.
US 20050082253 A1	US- PGPUB	20050421		Applying imprinting material to substrates	216/44	Cherala, Anshuman et al.

				employing electromagnetic fields			
US 20050067379 A1	US- PGPUB	20050331		Imprint lithography template having opaque alignment marks	216/44		Sreenivasan, Sidlgata V. et al.
US 20050064344 A1	US- PGPUB	20050324		Imprint lithography templates having alignment marks	430/320	101/3.1; 430/323	Bailey, Todd C. et al.
US 20050061773 A1	US- PGPUB	20050324		Capillary imprinting technique	216/44		Choi, Byung-Jin et al.
US 20050051698 A1	US- PGPUB	20050310		Conforming template for patterning liquids disposed on substrates	249/135		Sreenivasan, Sidlgata V. et al.
US 20050028618 A1	US- PGPUB	20050210		System for determining characteristics of substrates employing fluid geometries	73/865.9	425/169	Choi, Byung J. et al.
US 20050006343 A1	US- PGPUB	20050113		Systems for magnification and distortion correction for imprint lithography processes	216/59		Choi, Byung Jin et al.
US 20040251775 A1	US- PGPUB	20041216		Apparatus to control displacement of a body spaced-apart from a surface	310/311		Choi, Byung-Jin et al.
US 20040241324 A1	US- PGPUB	20041202		System for dispensing liquids	427/258		Watts, Michael P.C. et al.
US 20040223883 A1	US- PGPUB	20041111		System for determining characteristics of substrates	73/865.8	422/82.05; 702/108	Choi, Byung J. et al.

				employing fluid geometries			
US 20040223131 A1	US- PGPUB	20041111		Chucking system for modulating shapes of substrates	355/72	310/10; 310/12; 355/53; 378/34; 378/35	Choi, Byung J. et al.
US 20040211754 A1	US- PGPUB	20041028		Method of forming stepped structures employing imprint lithography	216/41		Sreenivasan, Sidlgata V.
US 20040200411 A1	US- PGPUB	20041014		Apparatus for fabricating nanoscale patterns in light curable compositions using an electric field	118/500	118/503	Willson, Carlton Grant et al.
US 20040188381 A1	US- PGPUB	20040930		Positive tone bi-layer imprint lithography method	216/40		Sreenivasan, Sidlgata V.
US 20040169441 A1	US- PGPUB	20040902		Apparatus to orientate a body with respect to a surface	310/328		Choi, Byung Jin et al.
US 20040168588 A1	US- PGPUB	20040902		Method of orientating a template with respect to a substrate in response to a force exerted on the template	101/150		Choi, Byung Jin et al.
US 20040149687 A1	US- PGPUB	20040805		Method of manufacturing a vacuum chuck used in imprint lithography	216/40		Choi, Byung Jin et al.
US 20040146792 A1	US- PGPUB	20040729		Magnification correction employing out-of-plane	430/22	264/293; 264/320; 264/339; 430/20;	Nimmakayala, Pawan K. et al.

				distortion of a substrate		430/322	
US 20040124566 A1	US- PGPUB	20040701		Step and repeat imprint lithography processes	264/494		Sreenivasan, Sidlgata V. et al.
US 20040112861 A1	US- PGPUB	20040617		Method for modulating shapes of substrates	216/66		Choi, Byung J. et al.
US 20040112153 A1	US- PGPUB	20040617		Method and system for determining characteristics of substrates employing fluid geometries	73/865.9		Choi, Byung J. et al.
US 20040104641 A1	US- PGPUB	20040603		Method of separating a template from a substrate during imprint lithography	310/328		Choi, Byung Jin et al.
US 20040090611 A1	US- PGPUB	20040513		Chucking system for modulating shapes of substrates	355/75	355/53; 355/72	Choi, Byung J. et al.
US 20040065976 A1	US- PGPUB	20040408		Method and a mold to arrange features on a substrate to replicate features having minimal dimensional variability	264/171.1	425/174; 425/175	Sreenivasan, Sidlgata V. et al.
US 20040065252 A1	US- PGPUB	20040408		Method of forming a layer on a substrate to facilitate fabrication of metrology standards	117/84		Sreenivasan, Sidlgata V. et al.
US 20040038552 A1	US- PGPUB	20040226		METHOD FOR FABRICATING BULBOUS-SHAPED VIAS	438/759	257/E21.025; 257/E21.259; 257/E21.578	Watts, Michael P.C. et al.

US 20040022888 A1	US- PGPUB	20040205		Alignment systems for imprint lithography	425/174.4	425/810	Sreenivasan, Sidlgata V. et al.
US 20040021254 A1	US- PGPUB	20040205		Alignment methods for imprint lithography	264/406	264/447; 264/496; 430/22	Sreenivasan, Sidlgata V. et al.
US 20040010341 A1	US- PGPUB	20040115		System and method for dispensing liquids	700/240		Watts, Michael P.C. et al.
US 20040009673 A1	US- PGPUB	20040115		Method and system for imprint lithography using an electric field	438/694	257/E21.024	Sreenivasan, Sidlgata V. et al.
US 20040008334 A1	US- PGPUB	20040115		Step and repeat imprint lithography systems	355/72	355/53; 355/67; 355/75	Sreenivasan, Sidlgata V. et al.
US 20040007799 A1	US- PGPUB	20040115		Formation of discontinuous films during an imprint lithography process	264/494		Choi, Byung Jin et al.
US 20030215577 A1	US- PGPUB	20031120		Method and system for fabricating nanoscale patterns in light curable compositions using an electric field	427/458	118/500; 118/503	Willson, Carlton Grant et al.
US 6990870 B2	USPAT	20060131		System for determining characteristics of substrates employing fluid geometries	73/865.9		Choi; Byung J. et al.
US 6986975 B2	USPAT	20060117		Method of aligning a template with a	430/22	430/30	Sreenivasan; Sidlgata V. et al.



				substrate employing moire patterns			
US 6982783 B2	USPAT	20060103		Chucking system for modulating shapes of substrates	355/72	355/53	Choi; Byung J. et al.
US 6980282 B2	USPAT	20051227		Method for modulating shapes of substrates	355/72	355/73; 355/75; 438/692	Choi; Byung J. et al.
US 6964793 B2	USPAT	20051115		Method for fabricating nanoscale patterns in light curable compositions using an electric field	427/466	427/256; 427/385.5; 427/595	Willson; Carlton Grant et al.
US 6955868 B2	USPAT	20051018		Method to control the relative position between a body and a surface	430/22	355/72; 396/428; 430/30	Choi; Byung Jin et al.
US 6932934 B2	USPAT	20050823		Formation of discontinuous films during an imprint lithography process	264/496	216/11; 216/52; 264/259; 264/293; 264/338; 264/40.1	Choi; Byung Jin et al.
US 6926929 B2	USPAT	20050809		System and method for dispensing liquids	427/256		Watts; Michael P. C. et al.
US 6922906 B2	USPAT	20050802		Apparatus to orientate a body with respect to a surface	33/613	33/644	Choi; Byung Jin et al.
US 6921615 B2	USPAT	20050726		High-resolution overlay alignment methods for imprint lithography	430/22	430/30; 430/322	Sreenivasan; Sidlgata V. et al.
US 6916585 B2	USPAT	20050712		Method of varying template	430/22	430/30; 430/322	Sreenivasan; Sidlgata V. et al.

				dimensions to achieve alignment during imprint lithography			
US 6916584 B2	USPAT	20050712		Alignment methods for imprint lithography	430/22	264/494; 264/496; 430/302; 430/322	Sreenivasan; Sidlgata V et al.
US 6908861 B2	USPAT	20050621		Method for imprint lithography using an electric field	438/694	257/E21.024; 438/708; 438/709; 438/714; 438/718; 438/725	Sreenivasan; Sidlgata V. et al.
US 6902853 B2	USPAT	20050607		Dual wavelength method of determining a relative position of a substrate and a template	430/22	356/399; 356/400; 356/401; 430/30	Sreenivasan; Sidlgata V. et al.
US 6900881 B2	USPAT	20050531		Step and repeat imprint lithography systems	355/72	355/78; 355/87	Sreenivasan; Sidlgata V. et al.
US 6873087 B1	USPAT	20050329		High precision orientation alignment and gap control stages for imprint lithography processes	310/323.17	310/328	Choi; Byung Jin et al.
US 6871558 B2	USPAT	20050329		Method for determining characteristics of substrate employing fluid geometries	73/865.8		Choi; Byung J. et al.
US 6870301 B2	USPAT	20050322		Method of separating a template from a substrate during imprint lithography	310/311	101/463.1; 430/320	Choi; Byung Jin et al.
US 6842229	USPAT	20050111		Imprint	355/75	355/72	Sreenivasan; Sidlgata

B2				lithography template comprising alignment marks			V. et al.
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